

| Ref # | Hits | Search Query   | DBs      | Default Operator | Plurals | Time Stamp       |
|-------|------|--|----------|------------------|---------|------------------|
| L1    | 1    | (cleaning and substrate and (insulator or dielectric or oxide) and (high\$k with dielectric) and (hydrogen with anneal) and (oxygen with anneal)).CLM. | US-PGPUB | OR               | ON      | 2005/11/17 16:10 |
| L2    | 3    | (substrate and (chamber or reactor) and ((loading or (heat with gas)) with treatment) and poly\$silicon). clm.   | US-PGPUB | OR               | ON      | 2005/11/17 16:18 |
| L3    | 1    | (substrate and (insulator or dielectric or oxide) and high\$k and anneal\$3 and ((loading or (heat with gas)) with treatment) and poly\$silicon).clm.  | US-PGPUB | OR               | ON      | 2005/11/17 16:19 |